

ABSTRACT

A light condenser suitable for EUV lithography that includes reflective rings concentric to an optical axis. Each ring has a reflective surface to reflect light rays emanating from a light source so that the light rays converge towards a mask to produce Köhler illumination on the mask. The reflective surface has a curve segment that includes a section of a parabolic curve that is rotated relative to an optical axis and has a focal point at the light source.

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